

09/432978

	Hits	Search Text	DBs
1	103	(organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	39	((organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)) and ((hydrogen H2 "H.sub.2" ) with (N2 "N.sub.2" nitrogen))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	12	etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same ((hydrogen H2 "H.sub.2" )with (N2 "N.sub.2" nitrogen))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	27	((((organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)) and ((hydrogen H2 "H.sub.2" ) with (N2 "N.sub.2" nitrogen))) not (etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same ((hydrogen H2 "H.sub.2" )with (N2 "N.sub.2" nitrogen)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
5	11	etch with (organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near antireflecti\$3) same (NH3 "NH.sub.3" ammonia)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	5648	((plasma and (resist photoresist) and ((metal\$3 aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN hard) near2 (mask\$3 layer film intermediate))) and (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj (k dielectric) low-k low-dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
7	15591	etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
8	0	(SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") and (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
9	0	etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
10	24655	plasma and (resist photoresist) and ((metal\$3 aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN hard) near2 (mask\$3 layer film intermediate))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
11	10041	(SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same etch\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
12	13979	(SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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13	13848	etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
14	365	((SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same etch\$3) and ((SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")) and (etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
15	134	(plasma and (resist photoresist) and ((metal\$3 aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN hard) near2 (mask\$3 layer film intermediate))) and (((SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same etch\$3) and ((SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same etch\$3) and ((SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj k low-k low adj dielectric BCB polyarylether ((organic polymer\$4) near (film layer)) organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ((ARC ARL ARF antireflecti\$3) near2 organic)) same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2")) and (etch\$3 same (((hydrogen H2 "H.sub.2" H2O "H.sub.2 O") with (N2 "N.sub.2" nitrogen)) NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine N2/H2 "N.sub.2 /H.sub.2" H2/N2 "H.sub.2 /N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
16	31	(US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.	USPAT; US-PGPUB
17	125	etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same (((hydrogen H2 "H.sub.2" with (N2 "N.sub.2" nitrogen NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
18	90	etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same (((hydrogen H2 "H.sub.2" with (N2 "N.sub.2" nitrogen NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
19	195	(etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same (((hydrogen H2 "H.sub.2" with (N2 "N.sub.2" nitrogen NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same (((hydrogen H2 "H.sub.2" with (N2 "N.sub.2" nitrogen NH3 "NH.sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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20	176	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
21	23	((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
22	87806	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and TiN WN TaN ((titanium tantalum tungsten) adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
23	74	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (TiN WN TaN ((titanium tantalum tungsten) adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
24	10	((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (TiN WN TaN ((titanium tantalum tungsten) adj nitride)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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25	2	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and polyaryl	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
26	76	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (low adj (k dielectric) low-k SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" BCB benzocyclobutane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
27	16	((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (low adj (k dielectric) low-k SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" BCB benzocyclobutane))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
28	25	<p>((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W)))</p> <p>((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
29	9	<p>((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W))) and (((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
30	9453	mask\$3 near2 (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN ((titanium tantalum tungsten) adj nitride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
31	18	((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (mask\$3 near2 (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN ((titanium tantalum tungsten) adj nitride)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
32	4	(((((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W))) and (((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
33	5	<p>(((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W)))</p> <p>(((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
34	910	<p>(interlevel adj dielectric ILD) same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" BCB benzocyclobutene polymer polymeric polyaryl (low adj (dielectric k)) low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic)</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
35	1	<p>((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and ((interlevel adj dielectric ILD) same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" BCB benzocyclobutene polymer polymeric polyaryl (low adj (dielectric k)) low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic))) and (((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or US-6013574-\$ or US-5796111-\$ or US-5358902-\$ or US-5266157-\$ or US-4528066-\$ or US-6417090-\$ or US-6331380-\$ or US-6281135-\$ or US-6268294-\$ or US-6265320-\$ or US-6235453-\$ or US-6207583-\$ or US-6204192-\$ or US-6165891-\$ or US-6211061-\$ or US-6350390-\$ or US-6413877-\$ or US-6372636-\$).did. or (US-20010034106-\$ or US-20010024769-\$ or US-20010027016-\$ or US-20020064941-\$ or US-20020127840-\$ or US-20020079054-\$ or US-20020059899-\$).did.) and (((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (aluminum copper cobalt tantalum platinum chromium tungsten titanium Al Cu Ta Pt Cr W))) and (((US-6114250-\$ or US-6124212-\$ or US-6080529-\$ or US-6042929-\$ or US-6017817-\$ or US-6030901-\$ or</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
36	19	<p>((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and ((interlevel adj dielectric ILD) same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" BCB benzocyclobutene polymer polymeric polyaryl (low adj (dielectric k)) low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic)))</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
37	33	<p>((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflecti\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine)))) and (hard adj mask\$3)</p>	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
38	15	<p>(US-6429107-\$ or US-6437441-\$ or US-6380091-\$ or US-6037255-\$ or US-6325861-\$ or US-6277752-\$ or US-6335249-\$ or US-6274471-\$ or US-6207570-\$).did. or (US-20010012687-\$ or US-20020081854-\$ or US-20020001931-\$ or US-20010030169-\$).did. or (EP-1030353-\$).did. or (EP-1030353-\$).did.</p>	USPAT; US-PGPUB; EPO; DERWENT



	Hits	Search Text	DBs
39	15	((US-6429107-\$ or US-6437441-\$ or US-6380091-\$ or US-6037255-\$ or US-6325861-\$ or US-6277752-\$ or US-6335249-\$ or US-6274471-\$ or US-6207570-\$).did. or (US-20010012687-\$ or US-20020081854-\$ or US-20020001931-\$ or US-20010030169-\$).did. or (EP-1030353-\$).did. or (EP-1030353-\$).did.) and ((etch\$3 same (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic near3 (layer film antireflect\$3)) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))) (etch\$3 same (SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutane ((polymer polymeric) near3 (film layer))) same ((hydrogen H2 "H.sub.2") with (N2 "N.sub.2" nitrogen NH3 "NH..sub.3" ammonia N2H4 "N.sub.2 H.sb.4" hydrazine))))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
40	4	surface adj wave adj interfered	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
41	1	1998JP-10-308836	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
42	16	"308836"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
43	7	"308836"	JPO; DERWENT
44	2	"10308836"	JPO; DERWENT
45	0	"10-308836"	JPO; DERWENT
46	0	"JP10308836"	JPO; DERWENT
47	0	"JP308836"	JPO; DERWENT
48	0	JP10-308836	JPO; DERWENT
49	0	JP-10-308836	JPO; DERWENT
50	42068 60	1998JP "10" "308836"	JPO; DERWENT
51	35235	(1998JP "10" "308836" ) and plasma	JPO; DERWENT
52	2410	((1998JP "10" "308836" ) and plasma ) and microwave	JPO; DERWENT
53	104	((((1998JP "10" "308836" ) and plasma ) and microwave) and suzuki	JPO; DERWENT
54	1	(((((1998JP "10" "308836" ) and plasma ) and microwave) and suzuki) and yokoshima	JPO; DERWENT
55	1	((((((1998JP "10" "308836" ) and plasma ) and microwave) and suzuki) and yokoshima) and (surface wave interfered)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
56	0	((((((1998JP "10" "308836" ) and plasma ) and microwave) and suzuki) and yokoshima) and (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutene polymer polymeric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
57	5	"880164"	EPO; DERWENT
58	3	(EP-880164-\$).did. or (EP-1189493-\$ or EP-880164-\$).did.	EPO; DERWENT
59	1	((EP-880164-\$).did. or (EP-1189493-\$ or EP-880164-\$).did.) and (polyaryl low adj k low-k organic-ARC organic-ARL organic-ARF org-ARC org-ARL org-ARF OARC OARL OARF BARC BARL BARF MARC MARL MARF ARC ARL ARF organic SiLk FLARE "SiLk.sup.tm" "FLARE.sup.tm" low adj dielectric BCB benzocyclobutene polymer polymeric)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
60	1	((EP-880164-\$).did. or (EP-1189493-\$ or EP-880164-\$).did.) and (aluminum copper cobalt tantalum platinum tungsten titanium Al Cu Ta Pt Cr W TiN WN TaN (titanium tantalum tungsten) adj nitride)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
61	0	((EP-880164-\$).did. or (EP-1189493-\$ or EP-880164-\$).did.) and metal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB